Dilute-nitride materials for mid-infrared photonics

The development of the dilute-nitride Sb- and As-based materials is triggered by their unique capability to access spectral range above 3µm for emitters and near 10µm for detectors preserving advantages offered by III-V type-I QW or bulk materials. The corresponding material development efforts are challenging and require comprehensive technological and experimental studies.

MBE methodology was established for growth of dilutenitride GaSbN and InAsN materials. Above 2% of nitrogen was incorporated into alloys.

Absorption and photoluminescence measurements demonstrated the allowed character of band edge optical transitions in dilute-nitride GaNSb and InAsN bulk materials.

Gradual bandgap reduction with nitrogen content was observed: ~200meV (GaSbN) and ~70meV (InAsN) per percent of nitrogen.

InAsN-based materials are currently being studied for the development of the nBn detectors.

HRXRD for Absorption for PL decay for bulk N=1.4% bulk N=0.3-1.4% bulk N=0.3-1.4% Room Temperature GaSb, N, on GaSb 8v10 N=1 4% 6x1(PL (c/s) N=0.7% 4x1(N=0.3% 0.55 0.60 0.30 0.35 0.45 0.50 0.40 Energy (eV) Time (ps)

GaSbN dilute-nitrides

Bandgap reduction ~200meV/%. Carrier lifetime in ps range.



InAsN dilute-nitrides

Bandgap reduction 70meV/%. Equilibrium PL observed.

